# Gain Measurement of Highly Stacked InGaAs Quantum Dot Laser with Hakki-Paoli Method

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## 1. Introduction

Quantum dot (QD) laser diode is attractive device to implement superior performance such as low threshold current [1] and higher speed modulation [2] because of three-dimensional carrier confinement.

However, it is difficult to fabricate large stacking of high density QD layers by conventional growth technique owing to the accumulation of strain [3, 4], which limits modal gain of QD laser. Recently the authors adopt ultrahigh-rate molecular beam epitaxial (MBE) growth technique which enables higher stacking and thinner spacer thickness [5-7], and demonstrated up to 19 stacked InGaAs QD laser diode with extremely short cavity length of 99- $\mu$ m [8].

In this work, we study net modal gain of these devices using Hakki-Paoli method [9, 10] and observed high maximum modal gain of  $68 \text{ cm}^{-1}$ .

# 2. Experimental

Using ultrahigh-rate MBE technique we fabricated 19 stacked  $In_{0.4}Ga_{0.6}As$  QD layer separated 20-nm-thick GaAs spacer layer on GaAs (001) substrate. This active region was sandwiched between the 1500-nm n-type  $Al_{0.3}Ga_{0.7}As$  lower-cladding layer and the 1500-nm p-type  $Al_{0.3}Ga_{0.7}As$  upper-cladding layer capped with 200 nm GaAs contact layer. After 50-µm-wide electrode was defined by photoli-thography technique. This wafer was craved into stripe laser device of 150-µm long cavity.

The device was subjected to a  $1-\mu$ s wide electric current pulse at a duty cycle of 1% at room temperature. The output power characteristic was measured by using an LD tester (Yuasa Electronic AT-143), and emission spectra were recorded by optical spectrum analyzer system (Yokogawa Electric AQ6370) with wavelength resolution of 0.05 nm.

# 3. Experimental result and discussion

Figure 1 shows the output power characteristic. The threshold current was 111 mA, corresponding to threshold current density of  $1.5 \text{ kA/cm}^2$ . High threshold current was owing to large mirror loss.

Figure 2 shows amplified spontaneous emission (ASE) spectrum observed at 68.6 mA, and ASE was observed at 1000 nm wavelength band (T-band) [11, 12]. The

Fabry-Perot mode spacing  $(\delta \lambda)$  of 0.87 nm was evaluated, from which effective refractive index (*n*) of 4 was obtained  $\delta \lambda$ .

The inset of Figure 3 shows gain spectra calculated by Hakki-Paoli method [9, 10] for two injection currents below threshold. The gain spectra  $g_{net}$  are given by

$$g_{net} = \frac{1}{L} \ln \frac{\gamma^{1/2} - 1}{\gamma^{1/2} + 1} + \frac{1}{L} \ln \frac{1}{R}$$
(1)

where *L* is cavity length of 150-µm, *R* is reflection coefficient calculated using the obtained value of *n*, and *y* is the peak-to-valley ratio [10] of the Fabry–Perot oscillations.

Figure 3 plots maximum gain for various injection currents. The maximum modal gain was 68 cm<sup>-1</sup> at 167.2 mA, which is larger than ~40 cm<sup>-1</sup>, the maximum gain reported for laser device with 10 stacked InAs QDs separated 35-nm-thick GaAs spacer on GaAs substrate [13]. The surface QD density of our laser and that of ref. 13 was approximately the same value of  $5 \times 10^{10}$  cm<sup>-2</sup> [6, 13]. These results indicates that highly stacking by using ultrahigh-rate MBE growth technique is more effective in getting large modal gain.

As the injection current increased, the wavelength blueshifts at a constant rate  $\Delta\lambda/\Delta I \approx 0.27$  nm/ mA for currents below 100 mA in the range of 1022–1028 nm. The cause of the blueshift can be assumed to be band filling.

#### 4. Conclusions

We measured gain spectra of 19-stacked InGaAs QD on GaAs substrate fabricated by ultrahigh-rate MBE growth technique using Hakki-Paoli method. High maximum modal gain of 68 cm<sup>-1</sup> was evaluated, and a blueshift of 0.27 nm/ mA for currents below 100 mA was observed, which can be attributed to band filling.

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Fig. 1 Output power vs injection current of the device.



Fig. 2 Amplified spontaneous emission (ASE) spectra obtained at injection current of 68.6mA.



Fig. 3 Maximum modal gain vs injection current. Inset: gain spectra operated at (a) 68.6 mA and (b) 107.2 mA.

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